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CLAIM AMENDMENTS

Claim 1. (presently amended) A method of removing a liquid from at least one surface of at least one substrate comprising the steps of:

subjecting said substrate to a rotary movement;

supplying a liquid on at least a part of said surface of said substrate; and

locally heating said liquid on said part of said surface, at a liquid ambient front ~~while supplying said liquid, wherein such that a sharply defined liquid ambient boundary is created, at least locally, while during the step of~~ subjecting said substrate to asaid rotary movement and supplying said liquid, at least locally a sharply defended liquid ambient boundary is created and

wherein said rotary movement is performed at a speed to guide the sharply defined liquid-ambient boundary over the substrate.

Claims 2-3. (cancelled)

Claim 4. (presently amended) A method as recited in claim 31, wherein said rotary movement is applied ~~onto~~ a single substrate such that said substrate rotates around its own ~~centre~~center.

Claim 5. (original) A method as in claim 4, wherein the rotation speed is in the range from 2 to 40 revolutions per second.

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Claim 6. (presently amended) A method as recited in claim 1, wherein said heating is accomplished by ~~means~~one of dispensing a heated gas; ~~or dispensing~~ a heated vapor; ~~or and~~ dispensing a heated mixture of a gas and a vapor.

Claim 7. (cancelled)

Claim 8. (presently amended) A method as recited in claim 1, wherein said liquid is comprises one of ~~a group of~~ an etching liquid, a cleaning liquid ~~or and~~ a rinsing liquid.

Claim 9. (presently amended) A method as recited in claim 1, wherein said liquid is comprises a dilute aqueous solution.

Claim 10. (presently amended) A method as recited in claim 8, wherein said cleaning liquid comprises one of a mixture of  $\text{NH}_4\text{OH}$ ,  $\text{H}_2\text{O}_2$  and  $\text{H}_2\text{O}$ ; ~~or comprises~~ a mixture of  $\text{HCl}$ ,  $\text{H}_2\text{O}_2$  and  $\text{H}_2\text{O}$ ; ~~or comprises~~ diluted  $\text{HCl}$ ; ~~or comprises~~ and a mixture comprising  $\text{O}_3$ .

Claim 11. (presently amended) A method as recited in claim 8, wherein said rinsing liquid comprises one of  $\text{H}_2\text{O}$ ; ~~or and~~ a mixture of  $\text{H}_2\text{O}$  and an acid, said mixture having a pH between 2 and 6.

Claim 12. (presently amended) A method of removing a liquid from a first surface and a second surface of at least one substrate comprising the steps of:  
subjecting said substrate to a rotary movement;

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supplying a liquid on at least a part of said first side and at least a part of said second side of said substrate; and

locally heating said liquid on said part of said first surface and on said part of said second surface; while supplying said liquid, ~~to thereby locally reduce such that~~ the surface tension of said liquid is locally reduced due to a surface tension gradient being formed in the liquid, the gradient being in a direction away from, wherein a sharply defined liquid-ambient boundary that is created, at least locally, during the steps of subjecting said substrate to a rotary movement, locally heating and supplying said liquid, at least locally a sharply defined liquid-ambient boundary is created and

wherein said rotary movement is performed at a speed to guide the sharply defined liquid-ambient boundary over the substrate.

Claim 13. (presently amended) An apparatus for removing a liquid from at least one surface of at least one substrate, said apparatus comprising:

a substrate holder which is subjectable to a rotary movement, said substrate being releasably held by said substrate holder;

at least one liquid supply system for applying a liquid on at least a part of said surface of said substrate;

at least one heat source for locally heating said liquid; and

said heat source and said liquid supply system being positioned such that said heating is applied closer to the ~~centre~~ center of said rotary movement of said substrate holder than said liquid and wherein said heat source and said liquid are positioned such that, at least locally, a sharply defined liquid-ambient boundary is created on said surface of said substrate.

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Claim 14. (presently amended) An apparatus as recited in claim 13, further comprising a chamber wherein said substrate holder is positioned, said chamber being designed in a manner to avoid back splashing of said liquid onto said surface of said substrate.

Claim 15. (presently amended) An apparatus as recited in claim 13, wherein said heating source comprises at least one nozzle for dispensing one of a heated gas; ~~or~~ a heated vapor; ~~or~~ and a heated mixture of a vapor and a gas onto said surface of said substrate, and said liquid supply system comprises at least one nozzle for applying said liquid on said part of said surface of said substrate, said nozzles are positioned such that said heating is applied closer to the ~~centre~~ center of the rotary movement of the substrate holder than said liquid.

Claim 16. (original) An apparatus as recited in claim 15, where said nozzles are mounted on an arm, said arm being movable relative to said substrate holder.

Claim 17. (cancelled)